

Figure 1.

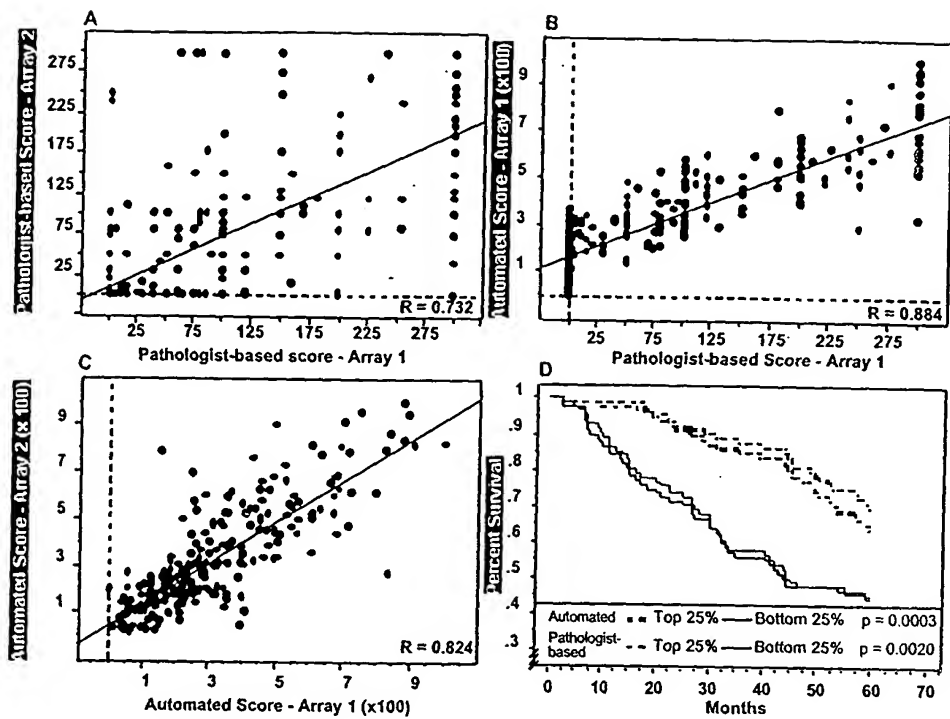
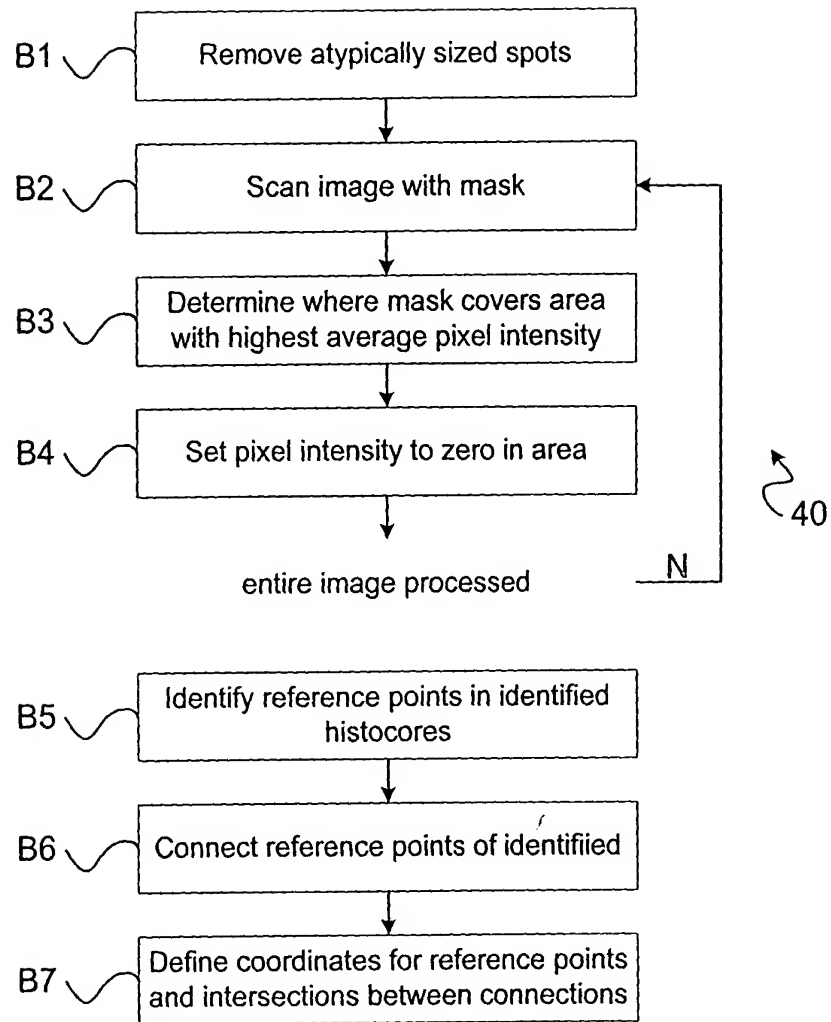
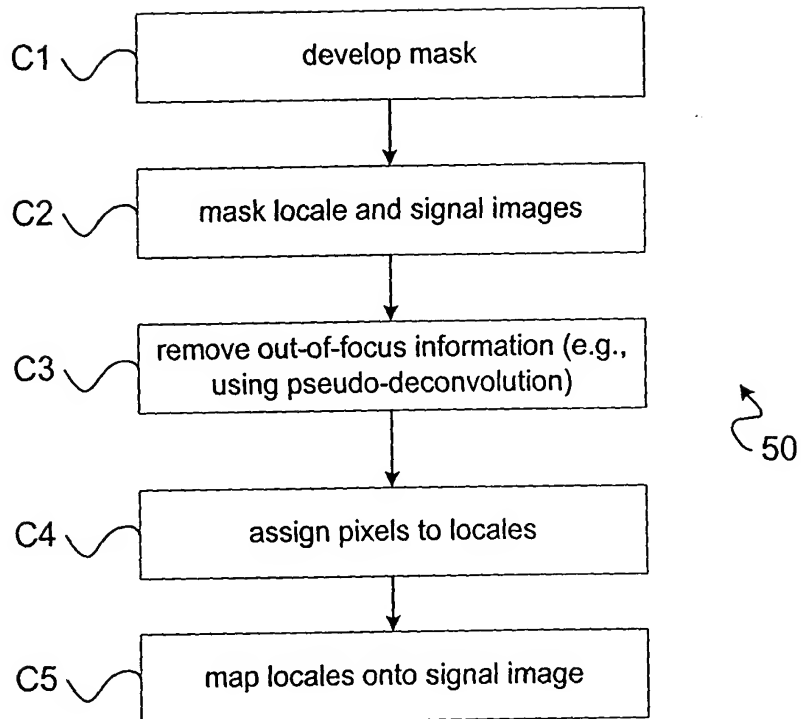


Figure 2



**FIG. 3**



**FIG. 4**

100  
↳

FIG. 5 is a schematic diagram of a device 100. The device 100 includes a substrate 110, a first layer 120, and a second layer 130. The first layer 120 is disposed on the substrate 110 and includes a grid of openings 120. The second layer 130 is disposed on the first layer 120 and includes a grid of openings 130. The openings 120 and 130 are aligned with each other.

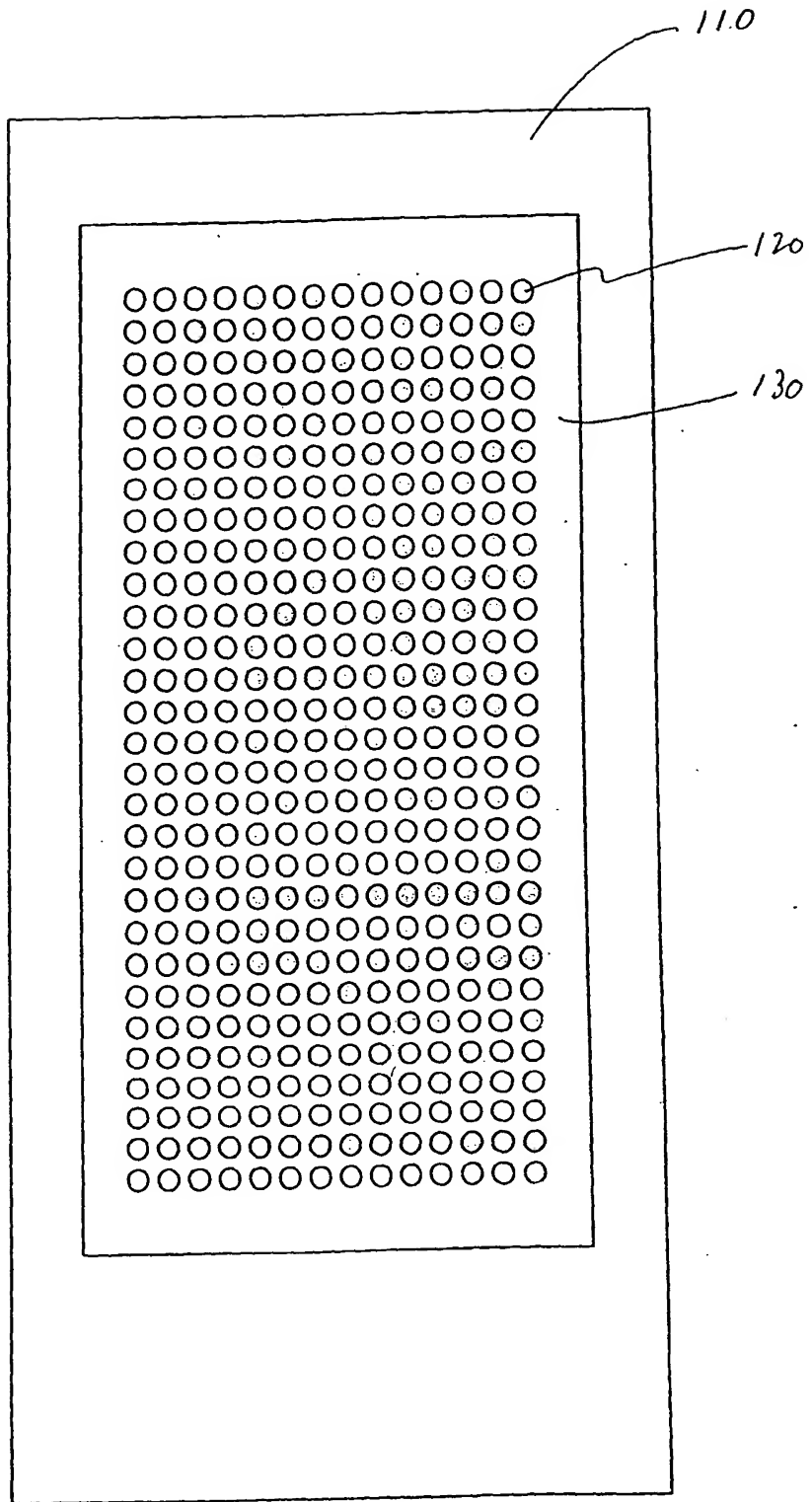


FIG. 5

FIG. 6 is a schematic diagram of a system 200 for processing a substrate 100. The system 200 includes a substrate 100, a processing chamber 210, a gas inlet 220, a gas outlet 230, a gas flow controller 240, a gas pressure controller 250, and a gas temperature controller 260. The system 200 is connected to a gas supply 270 and a gas exhaust 290.

200 →

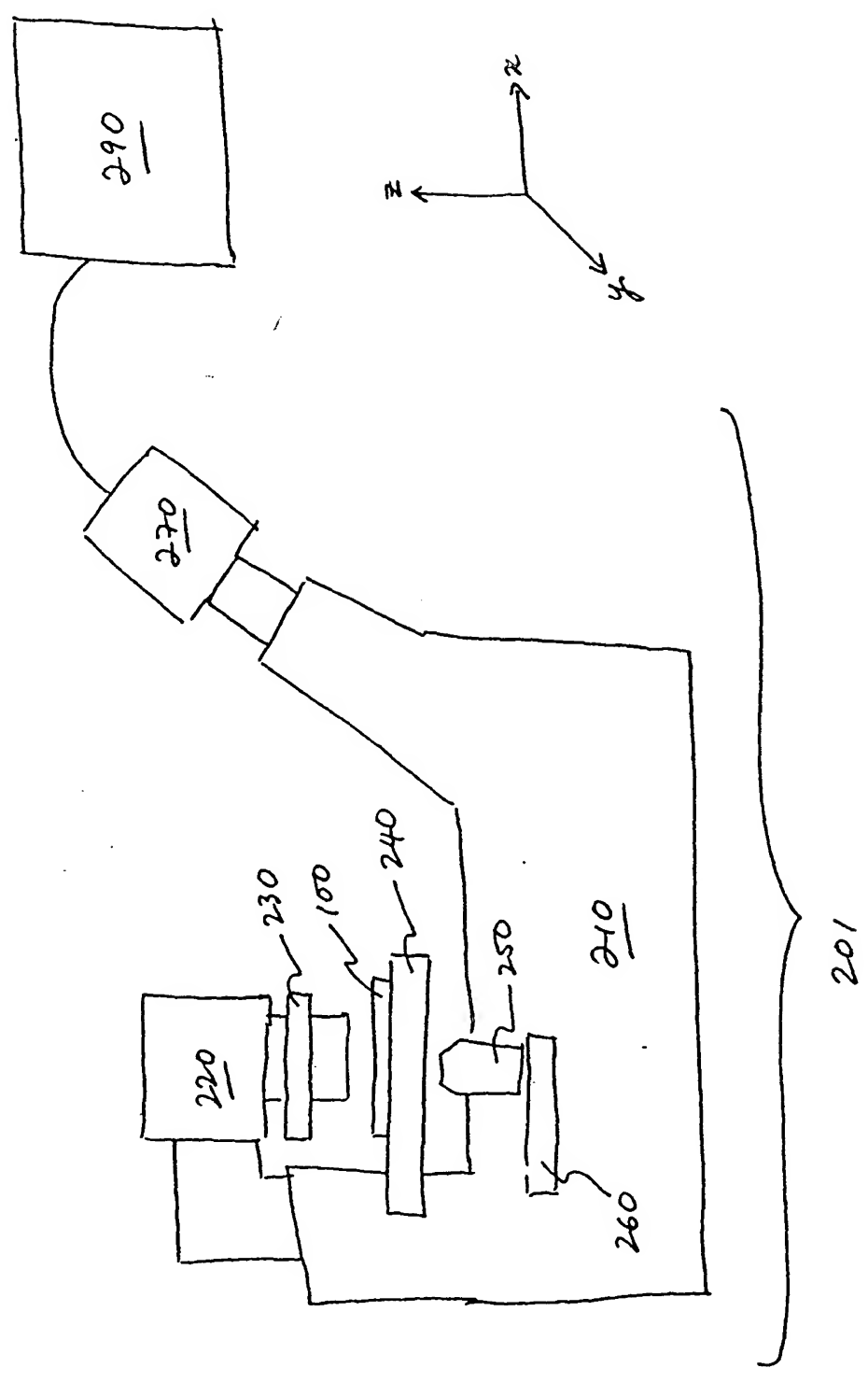


FIG. 6